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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 1

Complete if Known

Application Number	09/422,398
Filing Date	October 21, 1999
First Named Inventor	Bruce W. Smith
Group Art Unit	Unknown <i>285/</i>
Examiner Name	Unknown
Attorney Docket Number	88405.99R077

Sheet 1 of 1

U.S. PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No. ¹	Foreign Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Office ³	Number ⁴	Kind Code ⁵ (if known)		
HN	9	EP	0 503 472 A3	EP	Minori Noguchi	09/16/92
	10	EP	0 500 393 B1	EP	Akiyoshi Suzuki, et al.	08/26/92
	11	EP	0 500 393 A3	EP	Akiyoshi Suzuki, et al.	08/26/92
	12	EP	0 486 316 A3	EP	Naomasa Shiraishi	05/20/92
	13	EP	0 496 891 A1	EP	Naomasa Shiraishi	08/05/92
HN	14	EP	0 783 135 A1	EP	Akiyoshi Suzuki, et al.	07/09/97

**Examiner
Signature**

Nguyen, Hung Henry

Date
Considered

12/26/07

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¹ Unique citation designation number. ² See attached Kinds of U.S. Patent Documents. ³ Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). ⁴ For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. ⁵ Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. ⁶ Applicant is to place a check mark here if English language Translation is attached.

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**INFORMATION DISCLOSURE
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Sheet

2

of

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Complete If Known

Application Number	09/422,398
Filing Date	October 21, 1999
First Named Inventor	Bruce W. Smith
Group Art Unit	Unknown 2851
Examiner Name	Unknown
Attorney Docket Number	88405.99R077

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Ref. No.	Date	Examiner Initials	Title	Document Description
17	1999	HN	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", <u>J. Vac. Sci. Technology</u> , Vol B 10(6), pp. 3023-3026, (November/December 1992).
HN	16			E. Tamechika, et al., "Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", <u>J. Vac. Sci. Technology</u> , Vol. B 10(6), pp. 3027-3031, (November/December 1992).
HN	17			W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", <u>SPIE Optical/Laser Microlithography</u> , Vol. 1927, pp. 137-156, (1993).
HN	18			T. Ogawa, et al., "The Effective Light Source Optimization With the Modified Beam For the Depth-of-Focus Enhancements", <u>SPIE Optical Laser Microlithography</u> , Vol. 2197, pp. 19-30, (1994).
HN	19			T. Ogawa, et al., "Sub-Quarter Micron Optical Lithography With Practical Super Resolution Technique", <u>SPIE Optical Laser Microlithography VII</u> , Vol. 2440, pp. 772-783, (1995).
HN	20			B. W. Smith, et al., "Illumination Pupil Filtering Using Modified Quadrupole Apertures", <u>SPIE Optical Microlithography XI</u> , Vol. 3334, pp. 37-47, (1998).
HN	21			B.W. Smith, et al., "Influences of Off-Axis Illumination on Optical Lens Aberration", <u>J. Vac. Sci. Technology</u> , Vol. B16(6) 3398, pp. 3405-3410, (November/December 1998).
HN	22			Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 39-46, (1999).
HN	23			P. Zandbergen, et al., "Optical Extension at the 193nm Wavelength", <u>SPIE Optical Microlithography XI</u> , Vol. 3679, pp. 29-38, (1999).
HN	24			Z. Yang, et al., "Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", <u>SPIE International Lens Design Conference</u> , Vol. 1354, pp. 323-327, (1990).
HN	25			B. W. Smith, <u>Microlithography: Science and Technology</u> , Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.

Examiner Signature

Nugroho, Hung Henry

Date Considered

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